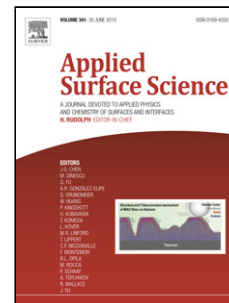


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A comparative study on the direct deposition of $\mu\text{c-Si:H}$ and plasma-induced recrystallization of a-Si:H: Insight into Si crystallization in a high-density plasma

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